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(72)Inventor : NISHIZAWA KEIICHIRO
SEGAWA HIDEAKI

(54) METHOD FOR REMOVING STRAIN IN QUARTZ GLASS

(57)Abstract:

PURPOSE: To remove strain in quartz glass without generating crystallization and almost keeping the previous shape before removing strain, by heating a quartz glass contg. strain at a temp. above a specified temp. in an inert-gaseous atmosphere.

CONSTITUTION: The strain in the quartz glass is removed by heating the quartz glass contg. strain at $\geq 1,200^{\circ}\text{C}$ in the inert gaseous atmosphere. A gas selected among rare gases and gaseous nitrogen, or a gaseous mixture of the above- mentioned gases is favorable as the inert gas. When the glass is heated at $\geq 1,500^{\circ}\text{C}$ order, the shape of the glass extremely changes because said glass is fluidized at that temp. A powder which is inert to the quartz glass is favorable to be packed around the quartz glass in order to prevent the change of shape. Powder of SiO_2 , C, SiC, stabilized ZrO_2 are exemplified as the powder to be packed.

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